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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re: Application of:

Chih-Ta Wu

Group Art Unit: 2891

Serial No.: 10/672,778

Examiner: Smith, Bradley

Filed: Sept. 26, 2003

In Response to Office Action

Dated: June 7, 2005

For: Atomic Layer Deposition (ALD) Method with Enhanced Deposition Rate

Attorney Docket No.: 67,200-940

Certificate of Mailing

I hereby certify that this paper is being deposited with the United States Postal Service on the date shown below with sufficient postage as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

R. TUNG 

7/5/05

RESPONSE TO OFFICE ACTION

Commissioner for Patents  
Alexandria, VA 22313-1450

In response to a restriction requirement imposed by the Examiner and mailed on June 7, 2005, the Applicants hereby elect with traverse, the prosecution of Group I, method claims 1, 2 and 5-24.